

ABSTRACT

A bilayer attenuating phase shift mask for use in photolithography having a phase shift layer and a layer of native oxide-free, elemental metal layer disposed on a substrate. The native oxide-free layer is chosen from platinum, palladium or a metal having like properties. A method of fabrication of the bilayer that uses the same etching ion to perform ion mill etching of the metal layer and chemical etching phase shift layer.

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